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		Application Number	10/694,284		
		Filing Date	10/27/2003		
		First Named Inventor	Xu et al.		
		Group Art Unit	Unassigned		
		Examiner Name	Unassigned		
Sheet	4	of	5	Attorney Docket Number	PA94-36-03

**OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS**

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
LH	A33	CHOU, "Nanoinprint Lithography and Lithographically Induced Self-Assembly," MRS Bulletin, July 2001, pp. 512-517.	
	A34	MIRKIN et al., "Emerging Methods for Micro-and Nanofabrication," MRS Bulletin, July 2001, pp. 506-509	
	A35	CHOI et al., "High Precision Orientation Alignment and Gap Control Stages for Imprint Lithography Processes," U.S. Patent Application 09/698,317, Filed with USPTO on October 27, 2000.	
	A36	BENDER M. et al., "Fabrication of Nanostructures using a UV-based Imprint Technique," Microelectronic Engineering, pp 223-236; 2000.	
	A37	SREENIVASAN et al., "High-Resolution Overlay Alignment Methods and Systems for Imprint Lithography," U.S. Patent Application Publication 2002/0098426. Published on July 25, 2002.	
	A38	CHOI et al., "Method and System of Automatic Fluid Dispensing for Imprint Lithography Processes," U.S. Patent Application Publication 2002/0094496. Published on July 18, 2002.	
	A39	CHOI et al., "Methods for High-Precision Gap and Orientation Sensing Between a Transparent Template and Substrate for Imprint Lithography," U.S. Patent Application Publication <del>2003/0093122</del> 2002/0093122. Published on July 18, 2002.	
	A40	Nguyen, A. Q., "Asymmetric Fluid-Structure Dynamics in Nanoscale Imprint Lithography," University of Texas at Austin, August 2001.	
	A41	WATTS et al., "Low Viscosity High Resolution Patterning Material," U.S. Patent Application Publication 2003/0235787. Published on December 25, 2003.	
	A42	WATTS et al., "System and Method for Dispensing Liquids," U.S. Patent Application Publication 2004/0010341. Published on January 15, 2004.	
LH	A43	SREENIVASAN et al., "Step and Repeat Imprint Lithography Systems," U.S. Patent Application Publication 2004/0008334. Published on January 15, 2004.	

Examiner Signature	<i>[Signature]</i>	Date Considered	6/8/04
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